L Number	Hits	Search Text	DB	Time stamp
3	2486	"silicon carbide layer"	USPAT; US-PGPUB; EPO; JPO;	2004/09/15 10:36
4	128	"silicon carbide layer" and (nitrogen with dope\$4)	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/09/15
5	24	"silicon carbide layer" and (nitrogen with dope\$4) and (leakage near4 current)	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/09/15 10:37
6	12	"silicon carbide layer" and (nitrogen with dope\$4) and (leakage near4 current) and "dielectric constant"	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/09/15
_	2	("5800878").PN. or ((2001/0030369) or (2002/0027286) or (2001/0051445) or (2001/0031563)).CCLS.	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/09/14 13:01
-	0	(2002/0027286) or (2001/0051445) or (2001/0031563)).CCLS.) and silicon and	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/09/14 13:02
-	124	carbon and nitrogen 438/624.ccls. and silicon and carbon and nitrogen	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/09/14 13:02
-	28	438/624.ccls. and silicon and carbon and nitrogen and "inert gas"	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/09/14 13:02
_	4	438/624.ccls. and silicon and carbon and nitrogen and "inert gas" and (electric with field)	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/09/14 13:03
-	4	438/624.ccls. and silicon and carbon and nitrogen and "inert gas" and (electric with field) and energy	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/09/14 13:03
-	4	438/624.ccls. and silicon and carbon and nitrogen and "inert gas" and (electric with field) and energy and RF	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/09/14 13:03
-	4	438/624.ccls. and silicon and carbon and nitrogen and "inert gas" and (electric with field) and energy and RF and power	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/09/14
-	2	438/624.ccls. and silicon and carbon and nitrogen and "inert gas" and (electric with field) and energy and RF and power	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/09/14 13:04
-	2	and electrode 438/624.ccls. and silicon and carbon and nitrogen and "inert gas" and (electric with field) and energy and RF and power	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/09/14
-	1	and electrode and plasma 438/624.ccls. and silicon and carbon and nitrogen and "inert gas" and (electric with field) and energy and RF and power	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/09/14
-	1	and electrode and plasma and "silicon carbide" 438/624.ccls. and silicon and carbon and nitrogen and "inert gas" and (electric with field) and energy and RF and power	DERWENT  USPAT;  US-PGPUB;  EPO; JPO;	2004/09/14 13:13
_	4	and electrode and plasma and "silicon carbide" 438/624.ccls. and silicon and carbon and nitrogen and "inert gas" and (electric	DERWENT  USPAT; US-PGPUB;	2004/09/14
		with field) and reaction	EPO; JPO; DERWENT	

-	4	438/624.ccls. and silicon and carbon and	USPAT;	2004/09/15
		nitrogen and "inert gas" and (electric	US-PGPUB;	10:36
		with field) and reaction and RF	EPO; JPO;	
			DERWENT	